

Abstract Submitted  
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**Universal behavior of surface-dangling bonds in hydrogen-terminated Si, Ge, and Si/Ge nanowires.**<sup>1</sup> RICARDO NUNES, Universidade Federal de Minas Gerais - UFMG, RICARDO KAGIMURA, HÉLIO CHACHAM, UFMG — We report an *ab initio* study of the electronic properties of surface dangling bond (SDB) states in hydrogen-terminated Si, Ge, and Si/Ge nanowires with diameters between 1 and 2 nm. We find that the charge transition levels  $\varepsilon(+/-)$  of SDB states are deep in the bandgap for Si wires, and shallow (near the valence band edge) for Ge wires. In both Si and Ge wires, the SDB states are localized. We also find that the SDB  $\varepsilon(+/-)$  levels behave as a “universal” energy reference level among Si, Ge, and Si/Ge wires within a precision of 0.1 eV. By computing the average between the electron affinity and ionization energy in the atom limit of several atoms from the III, IV and V columns, we conjecture that the universality is a periodic-table atomic property.

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